

EXHIBIT A.02
U.S. Patent No. 7,147,759

Ex. A.02.PDFReferences cited herein:

- U.S. Patent No. 7,147,759 (“759 Patent”)
- D.V. Mozgrin, *et al*, High-Current Low-Pressure Quasi-Stationary Discharge in a Magnetic Field: Experimental Research, Plasma Physics Reports, Vol. 21, No. 5, 1995 (“Mozgrin”)
- A. A. Kudryavtsev, *et al*, Ionization relaxation in a plasma produced by a pulsed inert-gas discharge, Sov. Phys. Tech. Phys. 28(1), January 1983 (“Kudryavtsev”)
- Li et al, Low-temperature magnetron sputter-deposition, hardness, and electrical resistivity of amorphous and crystalline alumina thin films, J. Vac. Sci. Technol. A 18(5), 2000 (“Li”)
- U.S. Pat. No. 6,413,382 (“Wang”)

Claims 10-12, 34-36	Mozgrin in view of Kudryavtsev and Li
<p>[1pre.] A magnetically enhanced sputtering source comprising:</p>	<p>The combination of Mozgrin with Kudryavtsev discloses a magnetically enhanced sputtering source.</p> <p>Mozgrin 403, right col, ¶4 (“Regime 2 was characterized by intense cathode <i>sputtering</i>...”) (emphasis added).</p> <p>Mozgrin at Fig. 1</p> <p>Figure 1 consists of two diagrams, (a) and (b). Diagram (a) is a cross-sectional view of a magnetron sputtering source. It shows a cathode (2) at the top and an anode (3) at the bottom. The cathode is a horizontal bar with hatched ends. The anode is a horizontal bar with a central gap. Magnetic field lines (B) are shown as arcs above the cathode and below the anode. Electric field lines (E) are shown as vertical arrows pointing from the cathode to the anode. A vertical z-axis and a horizontal r-axis are shown. Diagram (b) is a top-down view of the source. It shows the cathode (2) and anode (3) with magnetic field lines (B) and electric field lines (E) in detail. The magnetic field lines are shown as arcs above and below the cathode and anode. The electric field lines are shown as vertical arrows pointing from the cathode to the anode. A vertical z-axis and a horizontal r-axis are shown.</p>

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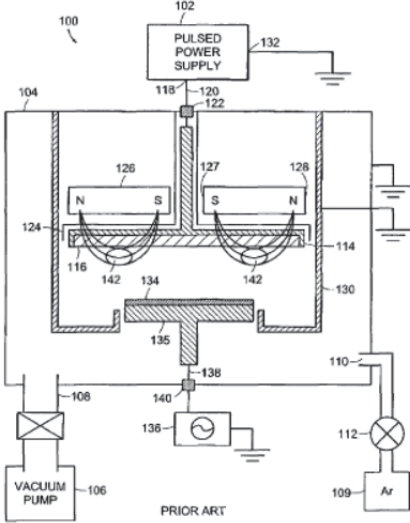
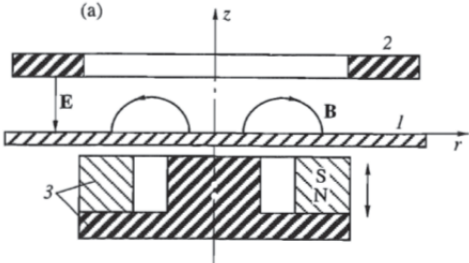
Claims 10-12, 34-36	Mozgrin in view of Kudryavtsev and Li
	<p>Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (1) Cathode; (2) anode; (3) magnetic system.</p>
<p>[1a.] an anode;</p>	<p>The combination of Mozgrin with Kudryavtsev discloses an anode. ‘759 Patent at Fig. 1</p>  <p align="center">PRIOR ART FIG. 1</p> <p>‘759 Patent at Fig. 1 (“FIG. 1 illustrates a cross-sectional view of a known magnetron sputtering apparatus having a pulsed power source.”) ‘759 Patent at 3:40-41 (“an anode 130 is positioned in the vacuum chamber 104 proximate to the cathode assembly.”)</p> <p>Mozgrin at Fig. 1</p> 

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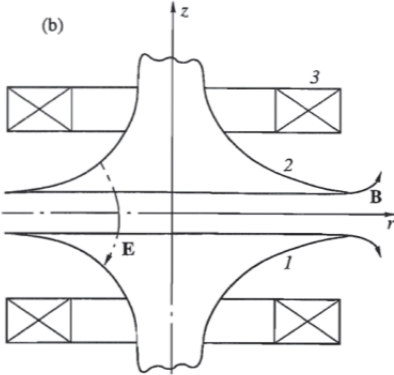
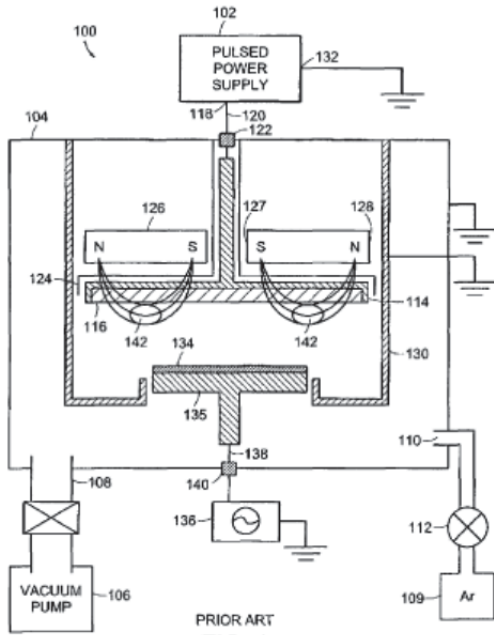
<p>Claims 10-12, 34-36</p>	<p align="center">Mozgrin in view of Kudryavtsev and Li</p>
	 <p>Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (1) Cathode; (2) anode; (3) magnetic system.</p>
<p>[1b.] a cathode assembly that is positioned adjacent to the anode, the cathode assembly including a sputtering target;</p>	<p>The combination of Mozgrin with Kudryavtsev discloses a cathode assembly that is positioned adjacent to the anode, the cathode assembly including a sputtering target.</p> <p>‘759 Patent at Fig. 1</p>  <p align="center">PRIOR ART FIG. 1</p> <p>‘759 Patent at 3:10-12 (“FIG. 1 illustrates a cross-sectional view of a known magnetron sputtering apparatus having a pulsed power source.”)</p> <p>‘759 Patent at 3:23-24 (“magnetron sputtering apparatus 100 also includes a cathode assembly 114 having a target material 116.”)</p>

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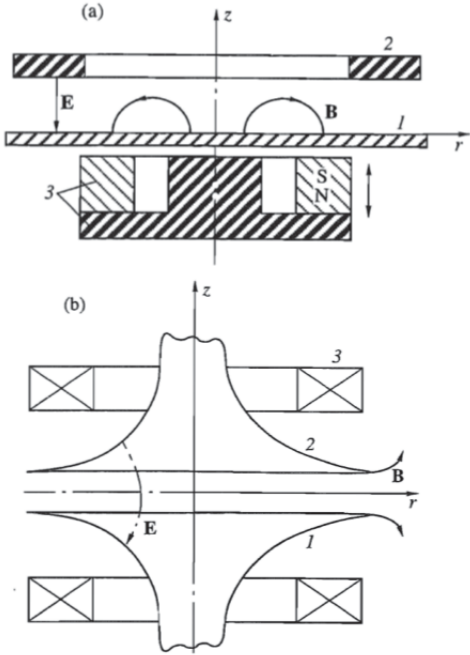
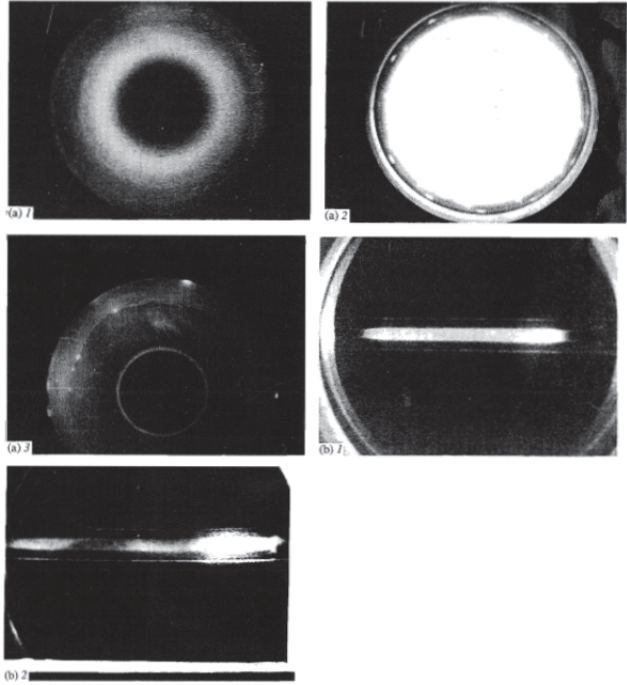
<p align="center">Claims 10-12, 34-36</p>	<p align="center">Mozgrin in view of Kudryavtsev and Li</p>
	<p>Mozgrin at 403, right col, ¶ 4 (“Regime 2 was characterized by intense cathode sputtering...”).</p> <p>Mozgrin at 403, right col, ¶ 4 (“...The pulsed deposition rate of the cathode material...”).</p> <p>Mozgrin at Fig. 1</p>  <p>Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (1) Cathode; (2) anode; (3) magnetic system.</p>
<p>[1c.] an ionization source that generates a weakly-ionized plasma proximate to the anode and the cathode assembly;</p>	<p>The combination of Mozgrin with Kudryavtsev discloses an ionization source that generates a weakly-ionized plasma proximate to the anode and the cathode assembly.</p> <p>‘759 Patent at 6:30-32 (“The weakly-ionized plasma is also referred to as a pre-ionized plasma.”)</p> <p>‘759 Patent at claim 32 (“wherein the peak plasma density of the weakly-ionized plasma is less than about 10^{12} cm⁻³”).</p> <p>Mozgrin at 401, right col, ¶2 (“For pre-ionization, we used a stationary magnetron discharge; the discharge current ranged up to 300 mA.... We found out that only the regimes with magnetic field strength not lower than 400 G provided the initial plasma density in the $10^9 - 10^{11}$ cm⁻³ range.”). (emphasis added).</p>

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<p style="text-align: center;">Claims 10-12, 34-36</p>	<p style="text-align: center;">Mozgrin in view of Kudryavtsev and Li</p>
	<p>Mozgrin at 401, left col, ¶ 1 (“The [plasma] discharge had an annular shape and was adjacent to the cathode.”). (emphasis added)</p> <p>Mozgrin at 402, right col, ¶2 (“Figure 3 shows typical voltage and current oscillograms.... Part I in the voltage oscillogram represents the voltage of the stationary discharge (pre-ionization stage).”).</p> <p>Mozgrin at Fig. 6</p>  <p>Fig. 6. High-current quasi-stationary discharge regimes. (a) planar magnetron: (1) high-current magnetron regime ($p = 10^{-1}$ torr, Ar, $I_d = 70$ A, $U_d = 900$ V); (2) high-current diffuse regime ($p = 10^{-1}$ torr, Ar, $I_d = 700$ A, $U_d = 80$ V); (3) arc regime ($p = 10^{-1}$ torr, Ar, $I_d = 1000$ A, $U_d = 45$ V). (b) Shaped-electrode system: (1) high-current diffuse regime ($p = 10^{-1}$ torr, Ar, $I_d = 1000$ A, $U_d = 45$ V); (2) contracted arc regime ($p = 10^{-1}$ torr, Ar, $I_d = 1500$ A, $U_d = 50$ V).</p>
<p>[1d.] a magnet that is positioned to generate a magnetic field proximate to the weakly-ionized plasma, the magnetic field substantially trapping electrons in the weakly-ionized plasma proximate to</p>	<p>The combination of Mozgrin with Kudryavtsev discloses a magnet that is positioned to generate a magnetic field proximate to the weakly-ionized plasma, the magnetic field substantially trapping electrons in the weakly-ionized plasma proximate to the sputtering target.</p> <p>‘759 Patent at 3:10-12 (“FIG. 1 shows a cross-sectional view of a known magnetron sputtering apparatus 100...” that has a magnet 126.”)</p> <p>‘759 Patent at 4:4-10 [<i>describing the prior art Fig. 1</i>] (“The electrons, which cause ionization, are generally confined by the magnetic fields produced by the magnet 126. The magnetic confinement is strongest in a confinement region 142....”)</p>

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